Docket No.: M4065.0715/P715
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
John T. Moore, et al.

Application No.: 10/614,160 Group Art Unit: 2818

Filed: July 8, 2003 Examiner: Not Yet Assigned

For: METHOD OF REFRESHINGA PCRAM MEMORY DEVICE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, DC 20231

Dear Sir:

Pursuant to 37 C.F.R. § 1.56, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached PTO/SB/08. It is respectfully requested that the subject matter of the documents be expressly considered during the prosecution of this application and that the documents be made of record therein and appear among the "References Cited" on any patent to issue form this application. A copy of each document is attached.

This Information Disclosure Statement accompanies the new patent application submitted herewith.

A brief explanation of relevance of the non-(U.S.)-patent documents listed on form PTO/SB/08 is provided and attached hereto as Appendix A. The brief explanation provided for each document is <u>not</u> tantamount to an admission that a document is "material" or that it qualifies as prior art. The Examiner is respectfully requested to utilize

Appendix A only as a tool by which to better categorize the documents for substantive use in examining the claims of the application.

Documents discussed in Appendix A marked with an asterisk (*) are indicated to be potentially more relevant than others. Such marking is provided only to assist the Examiner; however, the Examiner is requested to thoroughly review all documents cited herein.

In accordance with 37 C.F.R. § 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 C.F.R. § 1.56(a) exists. It is submitted that the Information Disclosure Statement is in compliance with 37 C.F.R. § 1.98 and the Examiner is respectfully requested to consider and cite the listed documents.

The Commissioner is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 04-1073, under Order No. **M4065.0715/P715.**

Dated: December 2, 2003

Respectfully submitted,

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APPENDIX A

U.S. Published Application No. 2003/0209971 to Kozicki: This document mentions in paragraph 90 that the disclosed memory cell only requires refreshing every several hours instead of every several nanoseconds as is the case with traditional DRAM cells.

U.S. Published Application No. 2003/0137869 to Kozicki: This document discloses in Fig. 4 and paragraph 68 a memory cell structure having a phase separated ion conductor 402, which includes high resistance portions 404 and low resistance portions 406.

U.S. Published Application No. 2003/0155589 to Campbell et al.: This document discloses a memory element formed as a stack of layers comprising a first electrode, a first chalcogenide glass, a silver-selenide layer, a second glass layer, and a second electrode.

Japanese patent application publication No. 56126916A by Akira: this published application generally relates to, <u>inter alia</u>, diffusing selenium with high accuracy into a chalcogenide with silver by use of photoresist and thermal treatment.

U.S. Patent No. 6,469,364 relates to a programmable interconnection system wherein a metal feature is created within the system by applying a voltage bias across the chalcogenide pathway. Voltages greater than 10 volts are applied to grow a metal dendrite and operating voltages are maintained below 5 volts to prevent unintentional growth of the metal dendrite. (col. 4 ln. 10-13).

*U.S. Published Applicant No. 2002/0072188 to Gilton: this document generally discloses a programmable variable resistance memory cell in which at least a variable resistance layer of the cell is formed in an isolated stack in an insulative layer.

* U.S. Published Applicant No. 2002/0123169 to Moore et al.: this document discloses a programmable variable resistance memory cell having a first conductive layer 16 formed in an opening in a first dielectric layer, a second conductive layer 18 formed on the first conductive layer. A layer of a chalcogenide material is formed in an opening in a second dielectric layer aligned with the opening in the first dielectric layer so that the chalcogenide material is formed on and over the first and second conductive layers, and a third conductive layer 32 is formed over the layer of chalcogenide material. *See* paras. 22, 28 and Fig. 8.

* U.S. Published Applicant No. 2002/0123248 to Moore et al.: this document discloses a programmable variable resistance memory cell having a first conductive layer 16 formed in an opening in a first dielectric layer, a second conductive layer 18 formed on the first conductive layer. A layer of a chalcogenide material is formed in an opening in a second dielectric layer aligned with the opening in the first dielectric layer so that the chalcogenide material is formed on and over the first and second conductive layers, and a third conductive layer 32 is formed over the layer of chalcogenide material. *See* paras. 22, 28 and Fig. 8.

U.S. Patent No. 5,177,567 to Klersy et al.: this document discloses a thin-film switching device having an electrode 1 formed on a substrate 7, a layer of insulating material 6 formed on the electrode 1, an opening formed in the insulating material to expose the electrode, a chalcogenide material 3 formed on the insulating material 6 and in the opening of the insulating material 6, a second electrode 5 on the chalcogenide

material 3, and a second and thick layer of insulating material 2 is deposited at least around the peripheral surface of the chalcogenide material.

* U.S. Patent No. 5,818,749 to Harshfield: this document discloses a reverse-biased diode memory array comprised of memory cells each having a structure changing memory element, such as chalcogenide resistors, coupled to an access device, such as a diode. *See, e.g.*, col. 6, lns. 36-47. Column 10, lines 12-59, *inter alia*, provides a discussion on the effects of current leakage into the substrate during operation of a forward-biased diode memory, as compared with the operation of a reverse-biased diode memory in which very little current leaks into the substrate.

U.S. Patent No. 5,920,788 to Reinberg: this document discloses memory cells constructed by first thermally growing an SiO_2 layer 35 on a substrate having isolation trenches formed therein. Apertures 40 are formed in the SiO_2 layer 35, whereupon electrode contact layers 55 60 and 65 are deposited in the apertures 40. The SiO_2 layer is further grown and then apertures 70 are formed in the SiO_2 layer. Chalcogenide layer 75 is then deposited over the SiO_2 layer 35 and into the apertures 70. Upper electrode contact layers 80 and 85 are formed on the chalcogenide layer 75 to thereby complete the memory cells 90.

*U.S. Patent No. 6,117,720 to Harshfield: this document generally discloses a plug-type stacked structure for a programmable variable resistance memory cell.

*U.S. Patent No. 6,236,059 to Wolstenholme et al.: this document generally discloses a stacked structure for a programmable variable resistance memory structure 55 partially formed in an opening 50 in a dielectric layer.

*U.S. Patent No. 6,300,684 to Gonzalez et al: this document discloses a programmable variable resistance memory cell 200 formed inside an opening 140, 215 formed in a substrate. *See, e.g.*, Figs. 14-15, col. 6, ln. 81 – col. 7, ln. 34.

*Kozicki, U.S. Patent No. 6,487,106 (2002): this patent discloses two embodiments shown in Figs. 2 and 3 which include a barrier layer 250, 350, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. (See col. 5, lns. 12-24; col. 7, lns. 7-17). Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570.

*Kozicki et al., U.S. Patent Application Publication No. 2002/0190350: this publication discloses in Figs. 5A, 6, 8 and 9 a structure having a substrate 510, 610, 810, 910; an insulating layer 520, 620, 820, 920; a bottom electrode 530, 630, 830, 930; an ion conductor 540, 640, 840, 940; a dielectric layer 550, 650, 850, 950; and a top electrode 560, 660, 860, 960. Fig. 5B discloses a structure having a bottom electrode 530, an ion conductor 540, an amorphous diode 562, and a top electrode 560.

*Moore et al., U.S. Patent Application Publication No. 2003/0001229: this publication discloses in Fig. 8 a memory cell structure comprising a substrate 12, a dielectric layer 14, another dielectric layer 17 with an opening formed therein, a first metal layer 16 deposited in the opening, a second metal layer 18 formed on the first metal layer 16, an insulating layer 30 formed over the second dielectric layer 17 with an opening formed therein to expose the second metal layer 18, a metal-doped chalcogenide layer 27 formed in the opening in the insulating layer 30 and over the second metal layer 18, and an electrode 32 formed over the metal-doped chalcogenide

layer 27. First metal layer 16 may be made from tungsten (paragraph 20) and the second metal layer 18 may be silver (paragraph 21).

*Moore et al., U.S. Patent Application Publication No. 2002/0127886: this publication discloses in Fig. 6 a memory cell structure comprising a substrate 10, an insulating layer 11, a conductive layer 12, a metal layer 31, a glass material layer 51, and an electrode 61. Conductive layer 12 may be made from tungsten (paragraph 17) and the metal layer 31 may be silver (paragraph 19).

Moore et al., U.S. Patent Application Publication No. 2002/0123170: this publication discloses in Fig. 6 a memory cell structure which includes a substrate 10, an insulating layer 11, a conductive material 12, a dielectric layer 13, a metal ion-laced glass material 51, a layer of metal material 41, and an electrode 61.

*Kozicki, U.S. Patent Application Publication No. 2003/0035314: this publication discloses a barrier layer 250, 350 as shown in Figs. 2 and 3 and discussed in paragraphs 35 and 45, respectively, formed between the layer of conductive material (such as chalcogenide material) 240, 340, respectively and the electrode 230, 330, respectively. Fig. 5 discloses a structure 502 including an amorphous silicon diode 570 formed adjacent to electrode 520, and a contact 560 formed adjacent the amorphous silicon diode 570, as discussed in paragraph 59.

*Kozicki, U.S. Patent Application Publication No. 2003/0035315: paragraph 70 on page 7 and Fig. 1 disclose a contact 165 electrically coupled to electrode 120, and which may be formed of tungsten. Paragraph 82 on page 8 and Fig. 4 disclose a structure 400 including an amorphous silicon diode 470 formed adjacent to electrode 420, and a contact 460 formed adjacent the amorphous silicon diode 470. Paragraph 102 on page 11 and Figs. 27-28 disclose a common electrode 2710, ion conductors 2730 and

2735, second electrodes 2720 and 2725, and an insulating layer 2750. The insulating layer 2750 is a dielectric layer "that does not interfere with surface electrodeposit growth, such as silicon oxides, silicon nitrides, and the like."

U.S. Patent Application 2002/0168820, Kozicki et al., published November 14, 2002, at Page 6 and Fig. 1, discloses a method of forming a microelectronic programmable device having a chalcogenide ion conductor formed between two electrodes. This application further discloses forming a chalcogenide ion conductor "using thermal and/or photo dissolution processing." (Page 5). Read, write, and erase operations for a silver-germanium selenide glass are also disclosed. (Page 7).

PCT Application WO 02/21542, Kozicki et al., published March 14, 2002, at Page 15 and Fig. 1, discloses a method of forming a microelectronic programmable device having an chalcogenide ion conductor formed between two electrodes. This application further discloses forming a chalcogenide ion conductor using "thermal and/or photo dissolution processing." (Page 11, lines 15-18). Read, write, and erase operations for a silver-germanium selenide glass are also disclosed. (Page 16, lines 10-30 and page 17, lines 1-26).

PCT Application WO 00/48196, Kozicki et al., published August 17, 2000, at Page 8, lines 20-30 and Fig. 1, discloses a method of forming a microelectronic programmable device having an chalcogenide ion conductor formed between two electrodes. This application further discloses forming a chalcogenide ion conductor using "thermal and/or photo dissolution processing." (Page 7, lines 12-15). Read, write, and erase operations for a silver-germanium selenide glass are also disclosed. (Page 10, line 21 through page 12, line 8).

U.S. Patent 6,418,049, Kozicki et al, filed Dec. 4, 1997, at Column 4, lines 28-67, discloses a "programmable sub-surface aggregating metallization structure" having a chalcogenide ion conductor and a plurality of electrodes. This patent further discloses forming a chalcogenide ion conductor using a photo dissolution process. (Column 4, lines

48-60). Application of voltage to the structure is disclosed at column 5, line 59 through column 6, line 53; column 7, line 28 through column 8, line 36; column 10, lines 22-37; and column 11, lines 35-52.

U.S. Patent 5,761,115, Kozicki et al., filed May 30, 1996, at Columns 4-5, discloses a "programmable metallization cell" having a chalcogenide ion conductor and a plurality of electrodes. This patent further discloses forming a chalcogenide ion conductor using a photo dissolution process. (Column 5, lines 32-45).

Abdel-All, et al., Vacuum 59 (2000) 845-853: published in December, this document generally relates to, inter alia, the electrical properties of $Ge_5As_{38}Te_{57}$ as a function of temperature.

*Adler and Moss, J. Vac. Sci. Technol. 9 (1972) 1182-1189: this document generally relates to, inter alia, two types of electrical/material switching – threshold and memory, in amorphous materials; the effects of temperature, pressure, and frequency on switching; and the physics of threshold voltage and memory.

Adler et al., Ref. Mod. Phys. 50 (1978) 209-220: this document generally relates to, inter alia, threshold switching in amorphous alloys, state ("on" and "off") characteristics, and glass properties.

Afifi, et al., Appl. Phys. A 55 (1992) 167-169: this document generally relates to, inter alia, SeGe-Sb glasses.

*Afifi, et al., J. Phys. 17 (1986) 335-342: this document generally relates to, inter alia, electrical and thermal conductivity of Ge_xSe_{1-x} compositions as a function of temperature. $Ge_{25}Se_{75}$ stoichiometry is disclosed.

Alekperova and Gadzhieva, 23 (1987) 137-139: this document generally relates to, inter alia, a characteristic diode state in Ag_2Se compositions upon heating (to 376-400°K).

*Aleksiejunas and Cesnys, Phys. Stat. Sol. (a) 19 (1973) K169-K171: this document generally relates to, inter alia, the subjects of selenium investigation and how Se-Ag_2Se contributes silver ions to a selenium composition.

Angell, Annu. Rev. Phys. Chem. 43 (1992) 693-717: this document generally relates to, inter alia, the presence of ion conductors in solids.

Aniya, Solid State Ionics 136-137 (November 2,2000) 1085-1089: this document generally relates to, inter alia, ion conductor glasses.

Asahara and Izumitani, J. Non-Cryst. Solids 11 (1972) 97-104: this document generally relates to, inter alia, Cu-As-Se glass.

Asokan, et al., Phys. Rev. Lett. 62 (1989) 808-810: this document generally relates to, inter alia, Ge_xSe_{100-x} glasses and their transition from semiconductor-like material to metal-like material.

*Axon Technologies Corp., *Technology Description*: *Programmable Metallization Cell*: this believed publication generally relates to, inter alia, use of chalcogenides doped with metal much as silver or copper to create solid state switch with lower voltage requirement.

Baranovskii and Cordes, J. Chem. Phys. 111 (1999) 7546-7557: this document generally relates to, inter alia, ionic glasses and conduction (percolation theory).

Belin et al., Sol. St. Ionics 136-137 (November 2,2000) 1025-1029: this document generally relates to, inter alia, conductivity spectra of the glass $0.5Ag_2S$-$0.5GeS_2$ and the temperature dependency of the conductivity.

Belin, et al., Solid State Ionics 143 (July 2, 2001) 445-455: this document generally relates to, inter alia, the electrical properties of Ag_7GeSe_5I – an argyrodite compound.

Benmore and Salmon, Phys. Rev. Lett. 73 (1994) 264-267: this document generally relates to, inter alia, the characteristics of chalcogenide alloys.

Bernede, Thin Solid Films 70 (1980) L1-L4: this document is in the French language and the Applicant has no translation. It is presently understood to generally relate to, inter alia, metal-Ag_2Se-metal sandwich devices.

Bernede, Thin Solid Films 81 (1981) 155-160: this document generally relates to, inter alia, memories of selenium alloys with metal (e.g., Ag) electrodes, where the "on" memory states require constant voltage.

Bernede, Phys. Stat. Sol. (a) 57 (1980) K101-K104: this document generally relates to, inter alia, metal-Ag_2Se-P systems.

Bernede and Abachi, Thin Solid Films 131 (1985) L61-L64: this document generally relates to, inter alia, metal-insulator-metal thin films with electroforming effects; the films have silver, gold and copper electrodes.

*Bernede, et al., Thin Solid Films 97 (1982) 165-171: this document generally relates to, inter alia, Ag_2Se/Se/Metal thin film sandwiches, which were studied by shape of electrodes (e.g., symmetrical or asymmetrical).

Bernede, et al., Phys. Stat. Sol. (a) 74 (1982) 217-224: this document generally relates to, inter alia, switching in Al-$Al_2O_3Ag_{2-x}Se_{1+x}$ devices.

Bondarev and Pikhitsa, Solid State Ionics 70/71 (1994) 72-76: this document generally relates to, inter alia, $Ag^{(-)}$/$RbAg_4I_5$ boundary – depletion layer, and dendritic electrodeposition.

*Boolchand, Asian Journal of Physics (2000) 9, 709-72: this document generally relates to, inter alia, Ge_xSe_{1-x} glasses, which have selenium-rich and germanium-rich clusters, and the intrinsically-broken bond characteristics thereof.

*Boolchand and Bresser, Nature 410 (2001) 1070-1073: published April 26, this document generally relates to, inter alia, Ag_2Se as an electrolyte additive to glass, e.g., $GeSe_4$. $Ge_{30}Se_{70}$ glass was found not to work well because of Ag_2Se crystallization.

*Boolchand, et al., J. Optoelectronics and Advanced Materials, 3 (September 2001), 703: this document generally relates to, inter alia, a review of Raman tool scattering of chalcogenide glasses. The floppyness and rigidness is observed. Ge_xSe_{1-x} is disclosed, as is a stoichiometry of $Ge_{25}Se_{75}$.

*Boolchand, et al., Properties and Applications of Amorphous Materials, M.F. Thorpe and Tichy, L. (eds.) Kluwer Academic Publishers, the Netherlands, 2001, pp. 97-132: this document generally relates to, inter alia, the prediction of glass rigidity in Ge_xSe_{1-x} glass, e.g., $Ge_{23}Se_{77}$.

*Boolchand, et al., Diffusion and Defect Data, Vol. 53-54 (1987) 415-420: this document generally relates to, inter alia, thermal annealing of Ge_xSe_{1-x} films.

*Boolchand, et al., Phys. Rev. B 25 (1982) 2975-2978: this document generally relates to, inter alia, the examination of GeSe glass having Sn impurities by Mossbauer spectroscopy. Investigations into glass network topology, which has an intrinsically broken bond backbone, suggesting Ge and Se rich clusters.

Boolchand, et al., Sol. State Comm. 45 (1983) 183-185: this document generally relates to, inter alia, Ge_xSe_{1-x} and Ge_xS_{1-x} glasses.

*Boolchand and Bresser, Dep. Of ECECS, Univ. Cincinnati 45221-0030: this document generally relates to, inter alia, Ge_xSe_{1-x} and the relation of glass transition temperature to Ge concentration in backbone. Although the publication date of this reference is not known to the Applicant, it was revised October 28, 1999 and is believed to be publicly available at the University of Cincinnati, Department of Electrical and Computer Engineering and Computer Science.

Boolchand and Grothaus, Eds. Chadi and Harrision, Proc. Int. Conf. Phys, Semicond., 17th (1985) 833-36: this document generally relates to, inter alia, GeSe and GeS glasses and the importance of a broken chemical order therein.

Bresser, et al., Phys. Rev. Lett. 56 (1986) 2493-2496: this document generally relates to, inter alia, an investigation of c-$GeSe_2$ structure.

Bresser, et al., J. de Physique 42 (1981) C4-193-C4-196: this document generally relates to, inter alia, the characteristics of $GeSe_2$ and GeS_2 glasses.

Bresser, et al., Hyperfine Interactions 27 (1986) 389-392: this document generally relates to, inter alia, germanium selenide glasses doped with tellurium.

Cahen, et al., Science 258 (1992) 271-274: this document generally relates to, inter alia, chalcopyrite $CuInSe_2$ glasses.

Chatterjee, et al., J. Phys. D: Appl. Phys. 27 (1994) 2624-2627: this document generally relates to, inter alia, $As_xTe_{100-x-y}Se_y$ glasses and the current, voltage, and electrical switching behavior. Discloses applicability in read mostly memories.

*Chen and Tai, Appl. Phys. Lett. 37 (1980) 1075-1077: this document generally relates to, inter alia, silver photodoping of Ge_xSe_{1-x} and whisker formation (crystalline Ag_2Se).

Chen and Cheng, J. Am. Ceram. Soc. 82 (1999) 2934-2936: this document generally relates to, inter alia, germanium containing chalcogenides doped with Si_3N_4.

Chen, et al., J. Non-Cryst. Solids 220 (1997) 249-253: this document generally relates to, inter alia, $As_{10}Ge_{30}Se_{60}$ glasses (and the like) doped with Si_3N_4.

Cohen, et al., J. Non-Cryst. Solids 8-10 (1972) 885-891: this document generally relates to, inter alia, Ge-Te-X glasses as memory devices.

Croitoru, et al., J. Non-Cryst. Solids 8-10 (1972) 781-786: this document generally relates to, inter alia, the physics of conductivity in Ge-containing films.

Dalven and Gill, J. Appl. Phys. 38 (1967) 753-756: this document generally relates to, inter alia, beta-Ag_2Te.

Davis, Search 1 (1970) 152-155: this document generally relates to, inter alia, the subject of amorphous semiconductors as compared to glass.

*Dearnaley, et al., Rep. Prog. Phys. 33 (1970) 1129-1191: this document generally relates to, inter alia, background information about glass and memory.

*Dejus, et al., J. Non-Cryst. Solids 143 (1992) 162-180: this document generally relates to, inter alia, Ag-Ge-Se glass with Ag primarily bonded to Se. The reference discloses glass preparation.

den Boer, Appl. Phys. Lett. 40 (1982) 812-813: this document generally relates to, inter alia, a-Si:H sandwich structures and threshold switching from a low to high conductance.

Drusedau, et al., J. Non-Cryst. Solids 198-200 (1996) 829-832: this document generally relates to, inter alia, work with a-Si:H multilayers optoelectrical properties.

El Bouchairi, et al., Thin Solid Films 110 (1983) 107-113: this document generally relates to, inter alia, $Ag_{2-x}Se_{1+x}$ thin film electrical characteristics and metal-like conduction.

El Gharras, et al., J. Non-Cryst. Solids 155 (1993) 171-179: this document generally relates to, inter alia, photoconductivity of amorphous Se and Ge-Se alloy evaporated films, and reduction of photocurrent by increase of Ge content.

*El Ghrandi, et al., Thin Solid Films 218 (1992) 259-273: this document generally relates to, inter alia, GeSe films deposited by PECVD, Ag evaporation deposition

onto glass and photodissolution into same, and optical properties are investigated. GeSe stoichiometries of 30/70 and 25/75, respectively, are disclosed.

*El Ghrandi, et al., Phys. Stat. Sol. (a) 123 (1991) 451-460: this document generally relates to, inter alia, dissolution of Ag into $GeSe_{5.5}$ glass by flash evaporation.

El-kady, Indian J. Phys. 70 A (1996) 507-516: this document generally relates to, inter alia, $Ge_{21}Se_{17}Te_{62}$ glass and memory, switching, and current controlled negative resistance.

Elliott, J. Non-Cryst. Solids 130 (1991) 85-97: this document generally relates to, inter alia, mechanisms of photodissolution of metals (e.g., Ag) in chalcogenides based on ionic and electronic charge carriers.

*Elliott, J. Non-Cryst. Sol. 130 (1991) 1031-1034: this document generally relates to, inter alia, the photodissolution of metals (e.g, Ag) in chalcogenide glasses and the physics thereof.

Elsamanoudy, et al., Vacuum 46 (1995) 701-707: this document generally relates to, inter alia, studies of quaternary chalcogenide films with Te-As-Ge-Si sandwich structures between electrodes.

*El-Zahed and El-Korashy, Thin Solid Films 376 (November 1,2000) 236-240: this document generally relates to, inter alia, $Ge_{20}Bi_xSe_{80-x}$ film analysis regarding conduction and changes from p to n type.

Fadel, Vacuum 44 (1993) 851-855: this document generally relates to, inter alia, a study of the switching and memory characteristics of $Se_{75}Ge_{25-x}As_x$ films.

*Fadel and El-Shair, Vacuum 43 (1992) 253-257: this document generally relates to, inter alia, $Se_{75}Ge_7Sb_{18}$ glass electrical conduction and thermal character.

Feng, et al., Phys. Rev. Lett. 78 (1997) 4422-4425: this document generally relates to, inter alia, germanium selenide and germanium sulfide materials.

*Feng, et al., J. Non-Cryst. Solids 222 (1997) 137-143: this document generally relates to, inter alia, the structural character of Ge_xS_{1-x} glass, e.g., hardness and elasticity.

*Fischer-Colbrie, et al., Phys. Rev. B 38 (1988) 12388-12403: this document generally relates to, inter alia, photodiffused Ag-$GeSe_2$ and the interaction between doped Ag with Se atoms and Ge with Ge atoms.

Fleury, et al., Phys. Stat. Sol. (a) 64 (1981) 311-316: this document generally relates to, inter alia, amorphous selenium films and their conductance.

Fritzsche, J. Non-Cryst. Sol. 6 (1971) 49-71: this document generally relates to, inter alia, background information on chalcogenides as semiconductors.

Fritzsche, Annual Review of Mat. Sci. 2 (1972) 697-744: this document generally relates to, inter alia, background information on amorphous semiconductors.

Gates, et al., J. Am. Chem. Soc. (2001): this document generally relates to, inter alia, creating Ag_2Se nanowires by chemical reaction.

Gosain, et al., Jap. J. Appl. Phys. 28 (1989) 1013-1018: this document generally relates to, inter alia, germanium telluride glasses sandwiched in electrodes and the physics thereof.

*Guin et al., J. Non-Cryst. Sol. 298 (March 28,2002) 260-269: this document generally relates to, inter alia, germanium selenide (GeSe) glass with low hardness, the mechanical properties of which are investigated. Stoichiometries of the glass are disclosed as being, inter alia, 10/90, 20/80, and 30/70, respectively.

*Guin et al., J. Am. Ceram. Soc. 85 (June 2002) 1545-1552: this document generally relates to, inter alia, germanium selenide glasses and a study of the hardness properties thereof. Glass stoichometries of 40/60 and 20/80, respectively, are disclosed.

Gupta, J. Non-Cryst. Sol. 3 (1970) 148-154: this document generally relates to, inter alia, switching in chalcogenides.

Haberland and Stiegler, J. Non-Cryst. Solids 8-10 (1972) 408-414: this document generally relates to, inter alia, glasses containing Te, As, Ge, and Si, and pulse sequence and time factors in switching.

Haifz, et al., J. Apply. Phys. 54 (1983) 1950-1954: this document generally relates to, inter alia, As-Se-Cu glasses.

Hajto, et al., Int. J. Electronics 73 (1992) 911-913: this document generally relates to, inter alia, metal/a-Si:H/metal devices.

Hajto, et al., J. Non-Cryst. Solids 266-269 (May 1,2000) 1058-1061: this document generally relates to, inter alia, a-Si:H ion conductors, polarity-dependant digital and analogue memory, and dependency on contact metals.

Hajto, et al., J. Non-Cryst. Solids 198-200 (1996) 825-828: this document generally relates to, inter alia, electroformed V/a-Si:H/Cr devices.

Hajto, et al., Phil. Mag. B 63 (1991) 349-369: this document generally relates to, inter alia, p+ type amorphous Si memory structures with polarity dependent analogue switching.

Hayashi, et al., Japan. J. Appl. Phys. 13 (1974) 1163-1164: this document generally relates to, inter alia, Au-CdS(CdSe)-Au systems and metal-Se-Sn-SnO_2 systems.

*Hegab, et al., Vacuum 45 (1994) 459-462: this document generally relates to, inter alia, $Ge_{20}M_{75}Sb_{18}$ glass electrical conduction and thermal character.

Helbert et al., SPIE Vol. 333 Submicron Lithography (1982): this publication generally relates to, inter alia, hybrid ultragraphic process using both electron beam and conventional optical exposure within the same device level with a photoresist.

Hilt, dissertation (1999): this publication generally relates to, inter alia, stability of chalcogenides such as Ge_xSe_{1-x} with Ag doping by photodissolution and thermal diffusion.

Hirose et al., Phys. Stat. Sol. (1980): this publication generally relates to, inter alia, switch and memory phenomena in amorphous As_2S_3 with photo-doped Ag, including new mechanism, electrical reliability, rapid memory performance, thermal characteristics and durability.

Hirose and Hirose, J. Appl. Phys. 47 (1976) 2767-2772: this document generally relates to, inter alia, Ag photodoped As_2S_3, polarized switching, and dendrite formation.

Holmquist et al., 62 J. Amer. Ceram. Soc., No. 3-4 (March-April 1979): this publication generally relates to, inter alia, reactions and diffusion of Ag in arsenic chalcogenide glass below the glass transition temperature, including solubility information and concentration dependence of Ag diffusion in these glasses.

Hong and Speyer, J. Non-Cryst. Solids 116 (1990) 191-200: this document generally relates to, inter alia, Cd-Ge-As glass with Ag contacts.

Hosokawa, J. Optoelectronics and Advanced Materials 3 (2001) 199-214: this document generally relates to, inter alia, x-ray scattering experiments on glassy Ge_xSe_{1-x}.

Hu, et al., J. Non-Cryst. Solids 227-230 (1998) 1187-1191: this document generally relates to, inter alia, a-Si:H with Cr and V electrodes.

Hu, et al., Phil. Mag. B. 74 (1996) 37-50: this document generally relates to, inter alia, a-Si:H glasses doped with Cr and analogue memory.

Hu, et al., Phil. Mag. B 80 (January 1, 2000) 29-43: this document generally relates to, inter alia, a-Si:H films doped with Cr-p+.

Huggett et al., 42 Appl. Phys. Lett., No. 7 (April 1983): this publication generally relates to, inter alia, reactive sputter etching to develop silver-sensitized Ge_xSe_{1-x} photoresist.

Iizima, et al., Solid State Comm. 8 (1970) 153-155: this document generally relates to, inter alia, switching and memory effects in As-Te-I[1,2] and As-Te-Ge-Si[3] glass systems. Thermal breakdown is proposed switching effect.

Ishikawa and Kikuchi, J. Non-Cryst. Solids 35 & 36 (1980) 1061-1066: this document generally relates to, inter alia, Ge_2S_2 films with Ag photodissolved therein.

*Iyetomi, et al., J. Non-Cryst. Solids 262 (February 2000) 135-142: this document generally relates to, inter alia, Ag/Ge/Se glasses as a composite of $GeSe_2$ and Ag_2Se (a fast ion conductor) and polarizability of Se ions.

Jones and Collins, Thin Solid Films 40 (1977) L15-L18: this document generally relates to, inter alia, switching in Se films and switching back with reverse pulse.

Joullie and Marucchi, Phys. Stat. Sol. (a) 13 (1972) K105-K109: this document generally relates to, inter alia, As_2Se_7 glass.

Joullie and Marucchi, Mat. Res. Bull. 8 (1973) 433-442: this document generally relates to, inter alia, As_2Se_5 film conduction and switching.

Kaplan and Adler, J. Non-Cryst. Solids 8-10 (1972) 538-543: this document generally relates to, inter alia, thermal effects on semiconductor switching.

Kawaguchi et al., 164-166 J. Non-Cryst. Solids (1993): this publication generally relates to, inter alia, deposition mechanism of Ag particles on Ag-rich Ag-As-S glass from a view-point of electrical effects.

*Kawaguchi, et al., J. Appl. Phys. 79 (1996) 9096-9104: this document generally relates to, inter alia, Ag-rich chalcogenide glass, Ge_3S_7-Ag and $Ge_{30}Se_{70}$-Ag, max Ag content of 67%, graphs phase diagram, and discloses that Ag works better than Cu.

*Kawaguchi and Masui, Japn. J. Appl. Phys. 26 (1987) 15-21: this document generally relates to, inter alia, silver photodoping of chalcogenide films, e.g., $Ge_{30}Se_{70}$ films.

*Kawasaki, et al., Solid State Ionics 123 (1999) 259-269: this document generally relates to, inter alia, the electrical properties of $Ag_x(GeSe_3)_{1-x}$, conductivity EMF measurements, glass composition, X-ray diffraction, T_g and T_c, Ag ion transport, and glass structure.

*Kluge, et al., J. Non-Cryst. Solids 124 (1990) 186-193: this document generally relates to, inter alia, photodiffusion of silver into Ge_xSe_{100-x} layers, how this differs from ion beam induced diffusion, $Ge_{30}Se_{70}$ stoichiometry, Ag_2Se, and percolation threshold.

*Kolobov, J. Non-Cryst. Solids 198-200 (1996) 728-731: this document generally relates to, inter alia, p-type conductive chalcogenides, materials, and physics thereof.

*Kolobov, J. Non-Cryst. Solids 137-138 (1991) 1027-1030: this document generally relates to, inter alia, doped and undoped glass layers as a p-n junction.

*Kolobov and Elliott, Advances in Physics (1991): this publication generally relates to, inter alia, photodoping (photodiffusion/photodissolution) of amorphous chalcogenides by metals, particularly silver.

Korkinova and Andreichin, J. Non-Cryst. Solids 194 (1996) 256-259: this document generally relates to, inter alia, polarization of chalcogenide glass as depending on the materials used for electrode contacts.

*Kotkata, et al., Thin Solid Films 240 (1994) 143-146: this document generally relates to, inter alia, GeSe glass switching and film thickness, memory, current filament, chemical and mechanical switching properties, and discloses that heat treatment or aging improves switching.

*Kozicki and Mitkova, Proceedings of the XIX International Congress on Glass, Society for Glass Technology (2001): this publication generally relates to, inter alia, the physical effects of introduction of Ag into chalcogenide glasses, where introduction is by photodiffusion.

*Michael N. Kozicki, Programmable Metallization Cell Technology Description, February 18, 2000: this publication generally relates to, inter alia, programmable metallization cells (PMC) for storing memory as resistive states. The PMC cells use a chalcogenide glass region bounded by electrodes as a memory device. The chalcogenide glass can be germanium selenide. The electrodes can be an oxidizable and indifferent material. Multiple-bit cells are disclosed; relying on controlling an amount of electrodeposit. Barrier layers of metal oxides, isolation diodes, and access transistors are also disclosed.

*Michael N. Kozicki, Axon Technologies Corp. and Arizona State University, Presentation to Micron Technology, Inc., April 6, 2000: this publication generally relates to, inter alia, programmable metallization cells (PMC) for storing memory as resistive states and operating parameters for PMC devices.

*Kozicki et al., Proceedings of the 1999 Symposium on Solid State Ionic Devices (1999): this publication generally relates to, inter alia, physical and electrical characteristics of metal doped chalcogenide films (photodoped $Ag_4As_2S_3$) between

electrodes, useful in memories, configurable connections, and self-repairing interconnections.

*Kozicki et al., Superlattices and Microstructures, 27 (2000): this publication generally relates to, inter alia, solid solutions of metals (e.g., silver) in arsenic trisulfide and their physical and electrical characteristics.

*Kozicki et al., Microelectronic Engineering, vol. 63/1-3 (2002): this publication generally relates to, inter alia, the photodiffusion of Ag into germanium selenide glass films, the amount of Ag that can be incorporated in to such a film by photodiffusion, and the characteristics of the resulting doped films.

Lakshminarayan, et al., J. Instn. Electronics & Telecom. Engrs. 27 (1981) 16-19: this document generally relates to, inter alia, tellurium-containing chalcogenide glasses.

Lal and Goyal, Indian Journal of Pure & Appl. Phys. 29 (1991) 303-304: this document generally relates to, inter alia, theory on chalcogenide switching.

*Leimer et al., Phys. Stat. Sol. (a) 29 (1975) K129-K132: this document generally relates to, inter alia, germanium selenide glass polarization behavior, e.g., inductive and capacitive components.

*Leung, et al., Appl. Phys. Lett. 46 (1985) 543-545: this document generally relates to, inter alia, photoinduced diffusion of Ag into Ge_xSe_{1-x} and techniques for same.

Matsushita, et al., Jap. J. Appl. Phys. 11 (1972) 1657-1662: this document generally relates to, inter alia, $Se\text{-}SnO_2$ film switching and reversibility.

Matsushita, et al., Jpn. J. Appl. Phys. 11 (1972) 606: this document generally relates to, inter alia, polarized memory effect in Se films.

Mazurier, et al., Journal de Physique IV 2 (1992) C2-185 - C2-188: this document generally relates to, inter alia, Te-based glasses.

McHardy et al., 20 J. Phys. C.: Solid State Phys. (1987): this publication generally relates to, inter alia, sensitivity and high resolution of metals in amorphous chalcogenides by electron and UV radiation.

Messoussi, et al., Mat. Chem. And Phys. 28 (1991) 253-258: this document generally relates to, inter alia, selenium films and Bi electrodes.

*Mitkova and Boolchand, J. Non-Cryst. Solids 240 (1998) 1-21: this document generally relates to, inter alia, the analysis of Group IV and V chalcogenides.

*Mitkova and Kozicki, J. Non-Cryst. Solids 299-302 (May 14, 2002) 1023-1027: this document generally relates to, inter alia, photodissolution of Ag into Se-rich Ge-Se glasses for use in memory devices. The information disclosed in this reference was available to and known by the inventors prior to the filing of the application.

*Mitkova, et al., Phys. Rev. Lett. 83 (1999) 3848-3851: this document generally relates to, inter alia, Ag doped chalcogenides, $Ge_{20}Se_{80}$ stoichiometry is disclosed, Se rich glasses, Ge rich glasses, stoichiometric glasses, and presence of Ag_2Se.

*Miyatani, J. Phys. Soc. Japan 34 (1973) 423-432: this document generally relates to, inter alia, electrical and ionic properties of solid solutions (e.g., doped glass), polarization, conductivity, Ag_2Se and Cu_2Se.

Miyatani, J. Phys. Soc. Japan 13 (1958) 317: this document generally relates to, inter alia, experiments regarding the electronic conductivity, ionic conductivity, hall constant, thermoelectric power, and Nernst coefficient of Ag_2Se as function of the e.m.f., E, the galvanic cell, or the deviation form stoichiometric composition.

*Miyatani, J. Phys. Soc. Japan 14 (1959) 996-1002: this document generally relates to, inter alia, Ag_2Te and Ag_2Se ion conduction and the chemical potential of silver ions.

Mott, J. Non-Cryst. Sol. 1 (1968) 1-17: this document generally relates to, inter alia, glasses with vanadium or iron.

*Nakayama, et al., Jpn. J. Appl. Phys. 32 (1993) 564-569: this document generally relates to, inter alia, electrically erasable nonvolatile memories in chalcogenide films of $As_xSb_yTe_z$, flash evaporative deposition techniques, a high set-voltage compared to read-voltage, V_t creates a "filament," and refresh-type pulse.

*Nakayama, et al., Jpn. J. Appl. Phys. 39 (November 15, 2000) 6157-6161: this document generally relates to, inter alia, phase transition random access memory (PRAM) made of chalcogenide glass.

*Nang et al., Jap. J. App. Phys. 15 (1976) 849-853: this document generally relates to, inter alia, Ge_xSe_{1-x} electrical and optical properties; it also discloses $Ge_{.80}Se_{.20}$, $Ge_{.60}Se_{.40}$, and $Ge_{.50}Se_{.50}$.

Narayanan, et al., Phys. Rev. B 54 (1996) 4413-4415: this document generally relates to, inter alia, chalcogenide glass switching as thermally originated.

*Neale and Aseltine, , IEEE Transactions On Electron Dev. Ed-20 (1973) 195-209: this document generally relates to, inter alia, read mostly memories with chalcogenides (e.g., Ge, Te), also discloses "floating gate," and material combinations including Ge and Se.

Ovshinsky and Fritzsche, Metallurgical Transactions 2 (1971) 641-645: this document generally relates to, inter alia, reversible changes in amorphous Si, Be, and B using a laser to write and erase.

Ovshinsky, Phys. Rev. Lett. 21 (1968) 1450-1453: this document generally relates to, inter alia, rapid and reversible resistive switching by electric field in amorphous semiconductors.

Owen, et al., IEE Proc. 129 (1982) 51-54: this document generally relates to, inter alia, a-Si:H, gold or aluminum dots and silver paste.

Owen, et al., Phil. Mag. B 52 (1985) 347-362: this document generally relates to, inter alia, photoinduced chalcogenide effects (As_2S_3) both reversible and irreversible.

*Owen, et al., Int. J. Electronics 73 (1992) 897-906: this document generally relates to, inter alia, threshold and memory switching a-Si:H ion conductor, polarity-dependant digital memory, analogue memory, and device operation dependency on metal contacts.

Owen et al., Nanostructure Physics and Fabrication (1989): this publication generally relates to, inter alia, photo-induced structural or physico-chemical changes of amorphous chalcogenides when exposed to light/irradiation, affecting chemical solubility.

Pearson and Miller, App. Phys. Lett. 14 (1969) 280-282: this document generally relates to, inter alia, glass diodes.

*Pinto and Ramanathan, Appl. Phys. Lett. 19 (1971) 221-223: this document generally relates to, inter alia, electric field inducement of glass switching “filamentary” path.

Popescu, Solid-State Electronics 18 (1975) 671-681: this document generally relates to, inter alia, the physics of chalcogenide switching.

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Popov, et al., Phys. Stat. Sol. (a) 44 (1977) K71-K73: this document generally relates to, inter alia, investigations into threshold and memory switching effects in amorphous selenium with electrodes of Ca, Ni, Ag, and Al.

*Prakash, et al., J. Phys. D: Appl. Phys. 29 (1996) 2004-2008: this document generally relates to, inter alia, switching of $Ge_{10}As_{45}Te_{45}$ glass, study of threshold voltage concept and switch back to off, suitability for read mostly memory.

Rahman and Sivarama, Mat. Sci. Eng. B12 (1992) 219-222: this document generally relates to, inter alia, chalcogenide glass with no exothermic crystallization reaction above T_g being of a threshold-switching type.

*Ramesh, et al., Appl. Phys. A 69 (1999) 421-425: this document generally relates to, inter alia, electrical switching in GeTe with Ag or Cu and thermal character investigations.

Rose, et al., J. Non-Cryst. Solids 115 (1989) 168-170: this document generally relates to, inter alia, a-Si with Cr or V contacts.

Rose et al., Mat. Res. Soc. Symp. Proc. V258 (1992) 1075-1080: this document generally relates to, inter alia, a-Si:H memory.

Schuocker and Rieder, J. Non-Cryst. Solids 29 (1978) 397-407: this document generally relates to, inter alia, As-Te-Ge film sandwiches with Molybdenum electrodes.

Sharma and Singh, Proc. Indian Natn. Sci. Acad. 46, A, (1980) 362-368: this document generally relates to, inter alia, evaporated Se films and their electrical conductivity.

*Sharma, Ind. J. Of Pure and Applied Phys. 35 (1997) 424-427: this document generally relates to, inter alia, n-type Ag_2Se and other material stoichiometries. The device conductivity is analyzed, as is the grain size as a factor in device ability to polarize.

Shimizu et al., 46 B. Chem Soc. Japan, No. 12 (1973): this publication generally relates to, inter alia, electric conductivity increase by increasing Ag-photodoping of chalcogenide glass.

Snell, et al., J. Non-Cryst. Solids 137-138 (1991) 1257-1262: this document generally relates to, inter alia, a-Si:H analogue memory by applying voltages of increasing magnitude.

Snell et al., Mat. Res. Soc. Symp. Proc. V 297 (1993) 1017-1021: this document generally relates to, inter alia, a-Si:H analogue memory.

Steventon, J. Phys. D: Appl. Phys. 8 (1975) L120-L122: this document generally relates to, inter alia, switching in chalcogenides, resistively changes, and formation of microfilaments at switch.

Steventon, J. Non-Cryst. Solids 21 (1976) 319-329: this document generally relates to, inter alia, chalcogenide switching with pulses and multiple pulse resetting.

Stocker, App. Phys. Lett. 15 (1969) 55-57: this document generally relates to, inter alia, switching character of bulk and thin film glasses.

Tanaka, Mod. Phys. Lett. B 4 (1990) 1373-1377: this document generally relates to, inter alia, photodoping mechanism and $Ag/As_{30}Se_{70}$.

Tanaka, et al., Solid State Comm. 8 (1970) 387-389: this document generally relates to, inter alia, thermal effect on switching in chalcogenides and As-Te-(Ge or Si).

*Thornburg, J. Elect. Mat. 2 (1973) 3-15: this document generally relates to, inter alia, division of chalcogenides into stoichiometric compounds with no changes upon crystallization, stoichiometric compounds with changes upon crystallization, and non-stoichiometric which phase separate on crystallization, As_2Se, and filament growth as a function of bias applied.

Thornburg, J. Non-Cryst. Solids 11 (1972) 113-120: this document generally relates to, inter alia, As_2Se_3 glass switching sandwich structure.

*Thornburg and White, (1972) 4609-4612: this document generally relates to, inter alia, precipitation of As particles out of As_2Se_3 glass and the alignment in a filament.

*Tichy and Ticha, J. Non-Cryst. Solids 261 (2000) 277-281: published in January, this document generally relates to, inter alia, Ge_xSe_{1-x} glass forming ability and 20/80 respective stoichiometry.

Titus, et al., Phys. Rev. B 48 (1993) 14650-14652: this document generally relates to, inter alia, percolation and chemical thresholds of chalcogenide glass.

*Tranchant, et al., Proceedings of the 6th Riso International Symposium. 9-13 September 1985: this document generally relates to, inter alia, GeSe glass with Ag, silver photodissolution, and generation of Ag_2Se.

Tregouet and Bernede, Thin Solid Films 57 (1979) 49-54: this document generally relates to, inter alia, Ag_2Te glass characteristics.

Uemura, et al., J. Non-Cryst. Solids 117-118 (1990) 219-221: this document generally relates to, inter alia, Ge_4Se_6 raman measurements and glass structure.

*Uttecht, et al., J. Non-Cryst. Solids 2 (1970) 358-370: this document generally relates to, inter alia, As-Te-Ge glass, V_t switching, filament formation, and reversal of voltage causes filament to grown in opposite direction.

Viger, et al., J. Non-Cryst. Solids 33 (1976) 267-272: this document generally relates to, inter alia, Se films dark-conductivity and photoconductivity.

*Vodenicharov, et al., Mat. Chem. and Phys. 21 (1989) 447-454: this document generally relates to, inter alia, M-GeSe-M films investigation for dc conductivity.

Wang, et al., IEEE Electron Dev. Lett. 13 (1992)471-472: this document generally relates to, inter alia, antifuses.

Weirauch, App. Phys. Lett. 16 (1970) 72-73: this document generally relates to, inter alia, chalcogenide device resistively changes in high electric fields.

*West, et al., J. Electrochem. Soc. 145 (1998) 2971-2974: this document generally relates to, inter alia, $Ag/As_{24}S_{36}Ag_{40}/Ag$ systems and Ag transport.

*West, Ph.D. Dissertation, ASU 1998: this document generally relates to, inter alia, metal dendrite memory with Ag or Cu doped solid electrolyte, photodissolution of Ag into As_2S_3 glass, lateral devices with silver electrodes, vertical devices with Ag electrodes, write voltages and lesser read voltages, and pinpoint electrode surrounded by ring electrode. Although the exact publication date for this document is not known, it is believed to be available at Arizona State University.

Zhang, et al., J. Non-Cryst. Solids 151 (1992) 149-154: this document generally relates to, inter alia, T_g investigation for glasses.

PTO/SB/08A (10-01)
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Complete if Known	
Application Number	10/614,160
Filing Date	July 8, 2003
First Named Inventor	John T. Moore, et al.
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Sheet	1	of	11

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Art Unit	4818
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U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.[1]	Document Number Number-Kind Code[2] *(if known)*	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	AA	2002/0000666	1/3/2002	Kozicki et al.	
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Sheet 3	of 11	Attorney Docket Number	M4065.0715/P715

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	BA	56126916	10/19981	Akira et al.		
	BB	WO 97/48032	12/18/1997	Kozicki et al.		
	BC	WO 99/28914	06/10/1999	Kozicki et al.		
	BD	WO 00/48196	08/17/2000	Kozicki et al.		
	BE	WO 02/21542	03/14/2002	Kozicki et al.		

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OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	10/614,160
	Filing Date	July 8, 2003
	First Named Inventor	John T. Moore, et al.
	Group Art Unit	4818
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